

ABSTRACT

Disclosed is a blank mask including a transparent substrate and a light shielding film disposed on the transparent substrate, wherein the light shielding film includes a transition metal and at least one selected from the group consisting of oxygen and nitrogen, wherein when a surface of the light shielding film includes nine sectors formed by trisecting the surface of the light shielding film vertically and horizontally, each of the nine sectors has a R_{sk} value, respectively, and an average value of the R_{sk} values of the nine sectors is equal to -0.64 or more and less than or equal to 0, where R_{sk} value is a height symmetry of the surface of the light shielding film measured in accordance with ISO_4287, and wherein an average value of R_{ku} values, which are kurtosis of the surface of the light shielding film measured in accordance with ISO_4287, of the nine sectors is 3 or less.

FIG. 1